

FORM PTO 1449 (modified)  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)  Date Submitted to PTO: <b>February 2, 2001</b>				ATTY DOCKET NO. <b>1960.30 DIV. I</b>		APPLICATION NO. <b>NYA</b>	
				APPLICANT <b>TIMOTHY M. RICHARDSONI</b>			
				FILING DATE <b>February 2, 2001</b>		GROUP <b>2877</b>	

PTO  
 09/773674  
 02/02/01

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLAS S	FILING DATE IF APPROPRIATE
<i>W.B.</i>		4,055,376	10/77	Daberko	350	10	
<i>W.B.</i>		5,622,796	4/97	Canestrari, et al.	430	22	
<i>W.B.</i>		4,616,241	10/86	Biefeld, et al.	357	16	
<i>W.B.</i>		4,947,223	8/90	Biefeld, et al.	357	30	
<i>W.B.</i>		5,027,178	6/91	Svilans	357	30	
<i>W.B.</i>		5,608,519	3/97	Gourley, et al.	356	318	

FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION YES/NO/ OR ABSTRACT
<i>W.B.</i>		0,214,1601	5/90	Europe	G01B	7/34	Abstract
<i>W.B.</i>		2,702,277	9/94	France	G01M	11/00	

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)		

EXAMINER <i>W.B.</i>	DATE CONSIDERED <i>23 Oct 2004</i>
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Sheet 1 of 2

FORM PTO 1449 (modified)		ATTY DOCKET NO. 1960.30 DIV. I	APPLICATION NO. NYA
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		APPLICANT TIMOTHY M. RICHARDSONI	
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W.D.		Electro-Optical Systems Design; OTF Quantitative Image Analysis; David Smith, Dec. 1979.	
W.D.		Cambridge University Press; Nanofabrication And Biosystems, H. Hoch, L.W. Jelinski, and H.G. Craighead.	
W.D.		Development In Semiconductor Microlithography; Testing The Mann Type 4800DSW™ Wafer Stepper™, W. Schneider, vol. 174, pp. 6-14 (1979)	
W.D.		JENOPTIK, Laser Optik Systeme	
W.D.		"Contrast Transfer In Confocal Microscopy" by R. Oldenbourg, et al.	
EXAMINER	DATE CONSIDERED		23 Oct 2001

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